

## BEST AVAILABLE COPY

Amendments to the Claims:

1. (Currently Amended) A method of analyzing plasma, said method comprising: igniting the plasma using an RF signal; using an RF signal monitor to monitor ~~monitoring~~ the RF signal as the RF signal is used to ignite the plasma; using an RF signal monitor to calculate ~~calculating~~ a value based on the RF signal; integrating the calculated value over a period of time; and plotting the integrated value to determine effects of a pre-determined parameter.
2. (Cancelled)
3. (Currently Amended) The method as recited in claim 1, further comprising plotting using the integrated value to determine ~~calculate~~ etch rate.
4. (Currently Amended) The method as recited in claim 1, further comprising plotting using the integrated value to determine ~~calculate~~ at least one etch chamber condition.
5. (Currently Amended) The method as recited in claim 1, further comprising plotting using the integrated value to determine ~~calculate~~ at least one of pressure, flow and gap spacing associated with an etch chamber.
6. (Currently Amended) The method as recited in claim 1, further comprising using a device separate from the RF signal monitor to integrate ~~integrating~~ a plurality of parts of the RF signal.

Serial No. 10/725,139

Art Unit: 2857

Page 2